

L Number	Hits	Search Text	DB	Time stamp
16	55	134/\$.ccls. and (ozone with (condens\$3 or cool\$3 or trap\$4)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:24
18	14	(ozone and (drain\$3 with condens\$3)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:25
17	34	(ozone with (condens\$3)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:28
19	14	(mist adj trap) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:28
20	12	((mist adj trap) and ozone) and (cool\$3 or condens\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:28
23	572	semitool.as.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:56
24	21	semitool.as. and (condens\$3 and ozone)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:57
39	49	(condensor) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:03
40	1	((condensor) and ((remov\$3 or strip\$4) with (resist or photoresist))) and (steam or vapor) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:03
41	4	8/149.3.ccls. and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:05
42	0	(8/149.3.ccls. and ozone) and condensor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:05
43	187	((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.) and (mist adj trap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:11
44	49	((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.) and (mist adj trap) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:10

45	19	(((((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.) and (mist adj trap)) and ((remov\$3 or strip\$4) with (resist or photoresist))) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:09
46	32	(((((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.) and (mist adj trap)) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:09
47	359	((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:11
48	8	(((((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.)) and (mist adj trap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:12
49	41	(tokyo adj electron).as. and (mist adj trap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:15
50	11	((tokyo adj electron).as. and (mist adj trap)) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:13
51	14	(tokyo adj electron).as. and ((remov\$3 or strip\$4) with (resist or photoresist)) and condens\$3 and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:15
52	170	438/\$.ccls. and ((remov\$3 or strip\$4) with (resist or photoresist)) and condens\$3 and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:24
53	113	(438/\$.ccls. and ((remov\$3 or strip\$4) with (resist or photoresist)) and condens\$3 and ozone) and drain\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:17
54	0	438/\$.ccls. and ((remov\$3 or strip\$4) with (resist or photoresist)) and condensor and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:37
55	1	(semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and condensor and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:46
56	1	(semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and (condensor with (solvent or vapor or steam))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:46
57	45	(semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and (condensor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:50

58	2584	(semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and (condensor or condenser)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:51
59	71	(semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and ((condensor or condenser) with (vapor or steam))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:51
60	12	((semiconductor or wafer or substrate) and ((remov\$3 or strip\$4) with (resist or photoresist)) and ((condensor or condenser) with (vapor or steam))) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:51
-	2211	134/902.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/18 15:25
-	62	134/902.ccls. and ozone and (steam or vapor) and heater	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/18 15:25
-	57	(134/902.ccls. and ozone and (steam or vapor) and heater) and control\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/18 15:26
-	103	(takayuki near2 toshima).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 08:25
-	62	(kinya near2 ueno).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 08:25
-	23	(miyako near2 yamasaka).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 08:26
-	14	(hideyuki near2 tsutsumi).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 08:26
-	216	(yuji near2 kamikawa).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 08:26
-	359	((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:06
-	128	134/\$.ccls. and semitool.as.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:56

-	92	134/\$.ccls. and (((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 09:48
-	13	(134/\$.ccls. and (((takayuki near2 toshima).in.) or ((kinya near2 ueno).in.) or ((miyako near2 yamasaka).in.) or ((hideyuki near2 tsutsumi).in.) or ((yuji near2 kamikawa).in.))) and ozone and (water or steam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 10:14
-	578	(remov\$3 with (resist or photoresist)) and ozone and (water or steam) and heater	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 10:50
-	416	((remov\$3 with (resist or photoresist)) and ozone and (water or steam) and heater) and (control\$4 with (heat\$3 or temperature))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 10:51
-	412	((remov\$3 with (resist or photoresist)) and ozone and (water or steam) and heater) and (control\$4 with (heat\$3 or temperature))) and (semiconductor or wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 10:51
-	80	((remov\$3 with (resist or photoresist)) and ozone and (water or steam) and heater) and (control\$4 with (heat\$3 or temperature))) and (semiconductor or wafer or substrate)) and 134/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:16
-	5050	134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:24
-	332	134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:24
-	24	(134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)) and (flow adj controller)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:43
-	230	(134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)) and (heat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:28
-	115	((134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)) and (heat\$3)) and (control\$4 with (temperature or heat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:55
-	3594	134/\$.ccls. and (control\$4 with (temperature or heat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:56
-	441	(134/\$.ccls. and (control\$4 with (temperature or heat\$3))) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:44

-	34	((134/\$.ccls. and (control\$4 with (temperature or heat\$3))) and ((remov\$3 or strip\$4) with (resist or photoresist))) and ((vessel or tank or chamber) with heater) and ((solvent or supply) with heater)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 14:57
-	1	(134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)) and (mist adj trap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:47
-	12	(mist adj trap) and (ozone adj killer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:40
-	12	((mist adj trap) and (ozone adj killer)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:41
-	15	(ozone adj killer) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:42
-	89	(134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (ozone) and (water or steam)) and (condens\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:43
-	78	ozone adj killer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:44
-	5	((ozone adj killer) NOT (tokyo.as.)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:57
-	65	(ozone adj killer) NOT (tokyo.as.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:45
-	10	134/58R,58R,95.2,98.1,99.1,102.1,102.3,105,200,902.ccls. and (mist adj trap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:47
-	142	134/\$.ccls. and (remov\$3 near2 ozone)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:53
-	2	134/\$.ccls. and (scrub\$4 near2 ozone)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:54
-	8	(scrub\$4 near2 ozone) same (condens\$3 or cool\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:56

-	4	((scrub\$4 near2 ozone) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:58
-	446	((remov\$3 or kill\$3 or destroy\$3 or decompos\$5 or scrub\$4) near2 ozone) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:08
-	294	((remov\$3 or kill\$3 or destroy\$3 or decompos\$5 or scrub\$4) near ozone) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 11:05
-	34	((remov\$3 or kill\$3 or destroy\$3 or decompos\$5 or scrub\$4) near ozone) same (condens\$3 or cool\$3)) and ((remov\$3 or strip\$4) with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/25 12:03